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A MODEL FOR OPTICAL ABSORPTION OF POROUS SILICON

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เจษฎา สุขพิทักษ์ : แบบจำลองการดูดกลื่นแสงของซิลิคอนรูพรุน. (A MODEL FOR OPTICAL ABSORPTION OF POROUS SILICON) อ. ที่ปรึกษา: รองศาสตราจารย์ ดร. วิชิต ศรีตระกูล, จำนวนหน้า 139 หน้า. ISBN 974-17-3311-9.

เราได้จำลองชิลิคอนรูพรุน ให้เป็นระบบไร้ระเบียบซึ่งประกอบขึ้นด้วยหลุมศักย์สามมิติซึ่งมี
การกระจายอย่างสุ่ม หลุมศักย์เหล่านี้เกิดขึ้นจากการนำอะตอมของชิลิคอนบางส่วนออกไปอย่างสุ่ม
จากผลึกสมบูรณ์ของชิลิคอน เราสามารถหาสมการเชิงวิเคราะห์ของความหนาแน่นสถานะเชิง
อิเล็กตรอนได้โดยการใช้เทคนิคการอินทิกรัลตามวิถีของฟายน์แมนสำหรับระบบไร้ระเบียบ การ
กระเพื่อมของศักย์อย่างสุ่มนี้เป็นสาเหตุทำให้เกิดสถานะเฉพาะถิ่นในส่วนหางของแถบพลังงานและ
ทำให้ช่องว่างแถบพลังงานกว้างขึ้นด้วย การกว้างขึ้นของช่องว่างแถบพลังงานนี้สามารถสังเกตได้จาก
ช่องว่างสภาพเคลื่อนที่ได้ของชิลิคอนรูพรุนและสามารถประเมินได้ว่าเป็นฟังก์ชันของค่าความพรุน เรา
ได้คำนวณหาค่าสัมประสิทธิ์การดูดกลืนเชิงแสงสำหรับค่าความพรุนโดยใช้แบบจำลองการดูดกลืน
อย่างง่ายร่วมกับความหนาแน่นสถานะที่ได้จากการคำนวณเพื่อที่จะพิจารณาช่วงของพลังงานที่การ
ดูดกลืนเชิงแสงมีส่วนเกี่ยวข้องอย่างมีนัยสำคัญกับการเปลี่ยนสถานะโดยไม่มีโฟนอนมาเกี่ยวข้อง ผล
จากการคำนวณชี้ให้เห็นว่าในการดูดกลืนเชิงแสงนั้นเราสามารถละทิ้งผลจากการเปลี่ยนสถานะโดย
ไม่มีโฟนอนมาเกี่ยวข้องได้อย่างมีเหตุผล นอกจากนี้เรายังวิเคราะห์ค่าความแรงของตัวกระเจิง
ประกอบกับผลการคำนวณการดูดกลืนเชิงแสงซึ่งแสดงให้เห็นถึงบทบาทที่สำคัญของการแจกแจง
ขนาดของผลึกขนาดนาโนเมตรในชิลิคอนรูพรุน

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We model porous silicon as a disordered system assembled of random distributing

three-dimensional quantum wells produced from random removals of some silicon atoms from a

perfect crystalline silicon. An analytic expression for its electronic density of states is

determined using Feynman's path integral technique for disordered systems. Random

fluctuations generated from disorder of the system create localized states in band tails as well

as band-gap widening. The latter effect could be observed from the mobility gap of porous

silicon, and can roughly be estimated as a function of its porosity. Optical absorption

coefficients with various values of porosity are determined using the obtained density of states

and a simple absorption model in order to investigate the energy range which significantly

involves with non-phonon assisted transitions. The calculation indicates that non-phonon

assisted processes can reasonably be neglected in optical absorption calculation for all values

of porosity of studies. The important role of nanocrystal size distribution of porous silicon is also

emphasized in the calculation as well as examination of scatterer strength.

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